

A LITHOGRAPHIC APPARATUS PROVIDED WITH A SWAP BRIDGE

ABSTRACT

A lithographic apparatus includes two stages that are each configured to hold a substrate, wherein each stage is provided with a short stroke module to move a table with a substrate and a long stroke module to move the short stroke module of that stage. The lithographic apparatus includes a swap bridge to couple the stages, and wherein, in use, in a first configuration, the stages are moveable with respect to each other, and wherein, in use, in a second configuration, the stages are coupled via the swap bridge to make a joint movement.

Figure 1